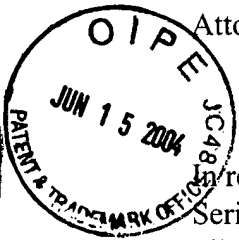


06-16-04

AP/1752  
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Attorney's Docket No. 5576-137

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Satoshi Watanabe

Confirmation No.: 3765

Serial No.: 10/052,687

Group Art Unit: 1752

Filed: January 18, 2002

Examiner: Thornton, Yvette C.

For: *RESIST MATERIAL AND PATTERN FORMING METHOD*

Date: June 15, 2004

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**REMARKS AFTER FINAL UNDER 37 C.F.R. §1.116**

Sir:

These Remarks are responsive to the Final Office Action ("Action") dated February 18, 2004 and are filed with a petition and fee for a one-month extension. Applicants provide the present Remarks to address the issues raised in the Action pursuant to the rules stated in revised 37 C.F.R. 1.121 that became effective on July 30, 2003.